

***MEMS Packaging reliability assessment
Residual Gas Analysis (RGA) of gaseous
species trapped inside MEMS cavity***

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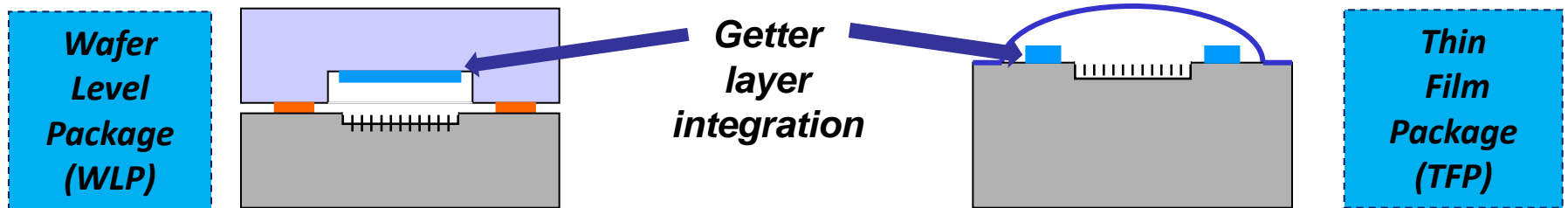
OUTLINE

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Vacuum requirements for MEMS packaged devices

- **Micro Electro Mechanical Sensors (MEMS) such as accelerometers, gyrometers, switches, μ bolometers usually require a minimum vacuum level** *** $P \leq 10^{-2}$ to 10^{-3} mb**

** avoid damping, sticking or conductives loss and chemical or moisture effect...).*



- **Tools required to control atmosphere inside MEMS sealed cavities**

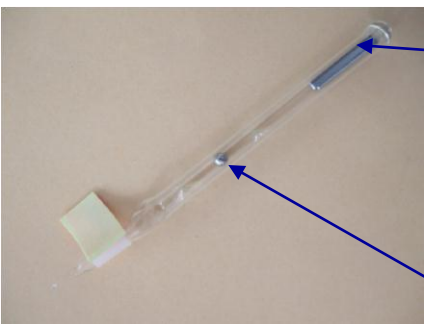
- **2 main goals**

- **1) Materials outgassing or pumping & compatibility with process**

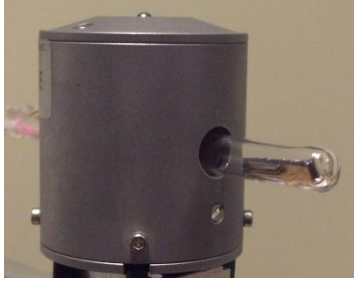
- **2) Residual Gas Analysis of atmosphere inside MEMS sealed cavities**

Tools developed at LETI for atmosphere control

1) Materials outgassing or pumping & compatibility with process

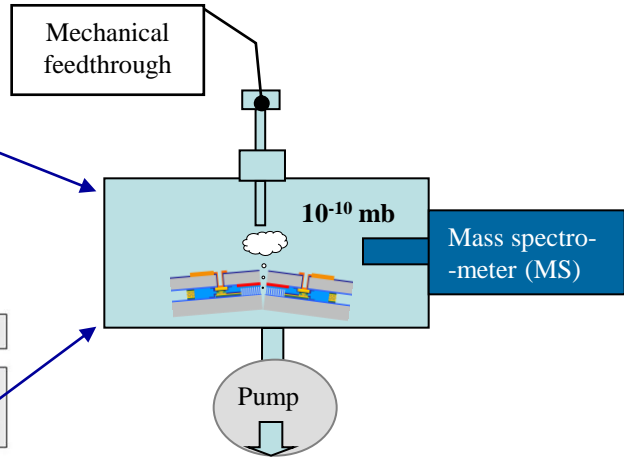
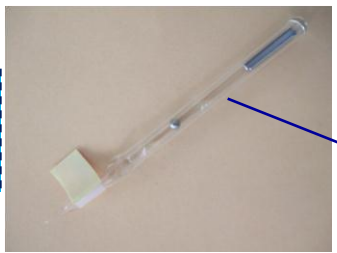


- Sample under specific gases (N_2 , Ar, CO_2 , CH_4 , C_2H_6 , ...)
- Thermal activation to study outgas or getter effects
- Pressure measurement with spinning rotor gauge

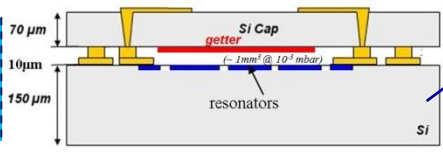


2) Residual Gas Analysis in UHV chamber

$V=2.5 \text{ cm}^3$, $P=10^{-3} \text{ mb}$
 $N_{\text{moles}} \sim 10^{-10}$

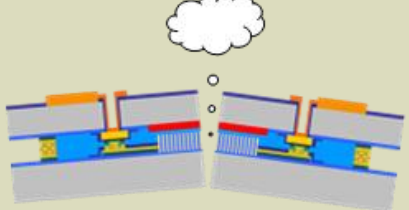


$V=1 \text{ mm}^3$, $P=10^{-3} \text{ mb}$
 $N_{\text{moles}} \sim 4 \cdot 10^{-14}$



RGA applications:

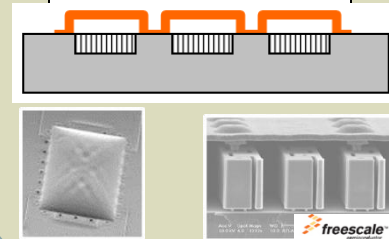
Wafer Level Package
MEMS



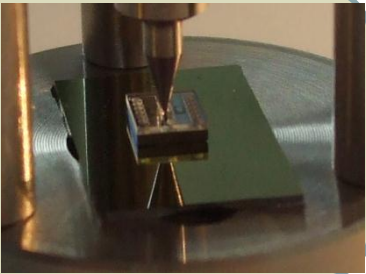
Glass bulbs for material
thermal studies



Thin Film Package
MEMS



Break
ing
UHV
tools



Scratch
UHV
tools



RGA

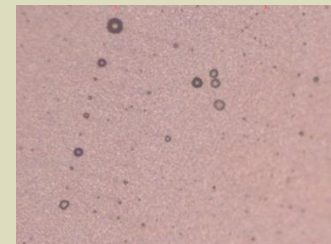
Device in case



Gases sampled in an
UHV container

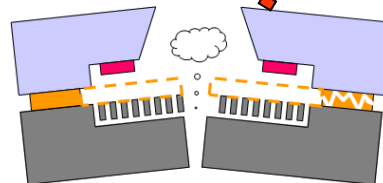
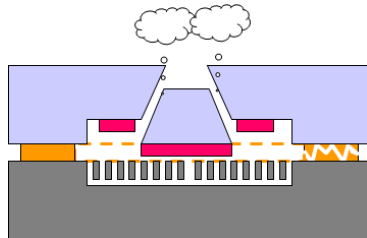
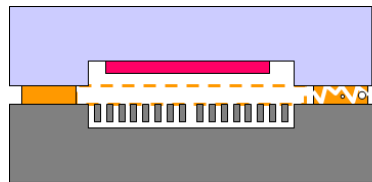
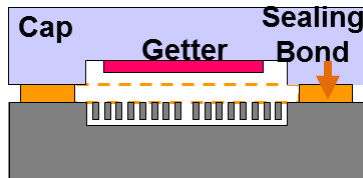


Gas bubbles on a surface



RGA applications: an exemple on a sealed MEMS

Question: Identified on a sealed MEMS the # outgassing sources

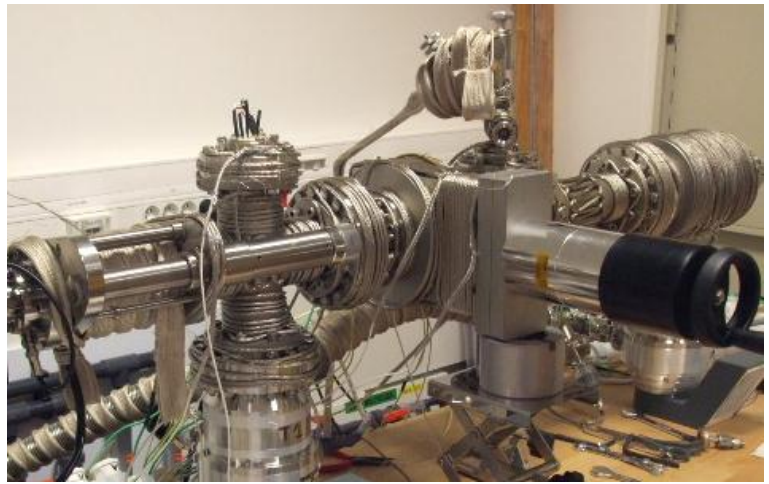
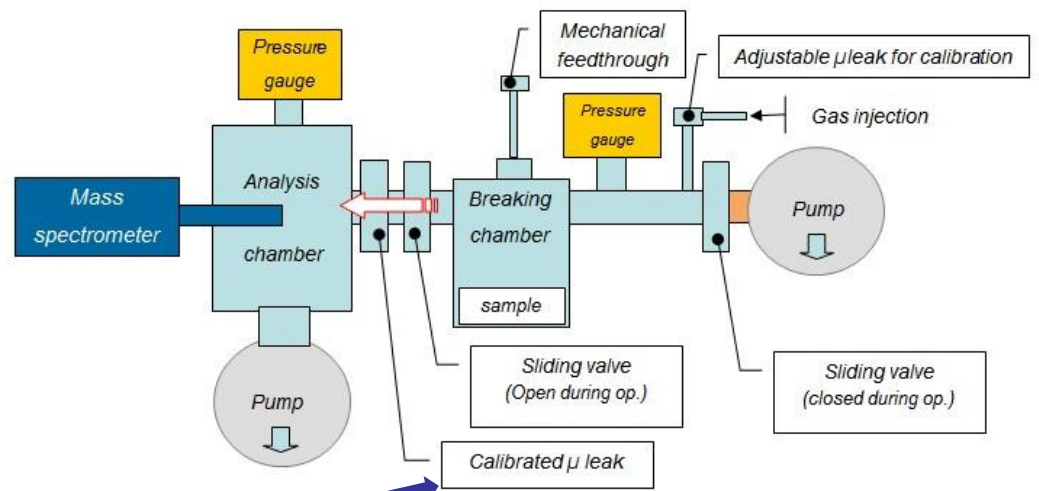


moles	CH_4	N_2	Ar	C_2H_6	...
<i>cavity</i>	?	?	?	?	
<i>cap</i>	?	?	?	?	
<i>Substrate</i>	?	?	?	?	

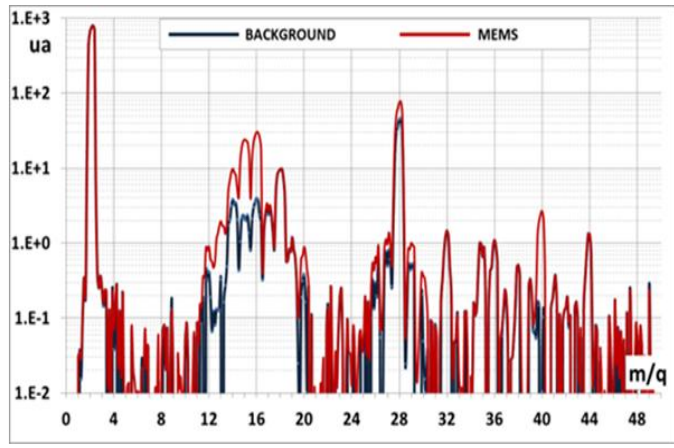
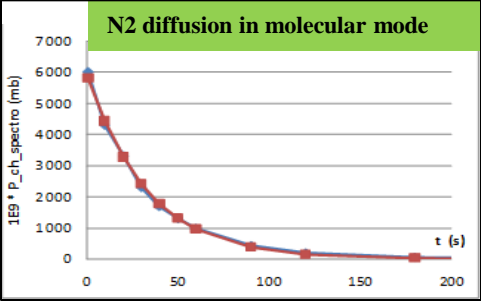
*Possible in some case
with specific tools*

RGA Bench

Schematic of the set-up.



Gases diffuse through a calibrated μleak (diaphragm)



Typical spectrogram performed during an RGA experiment

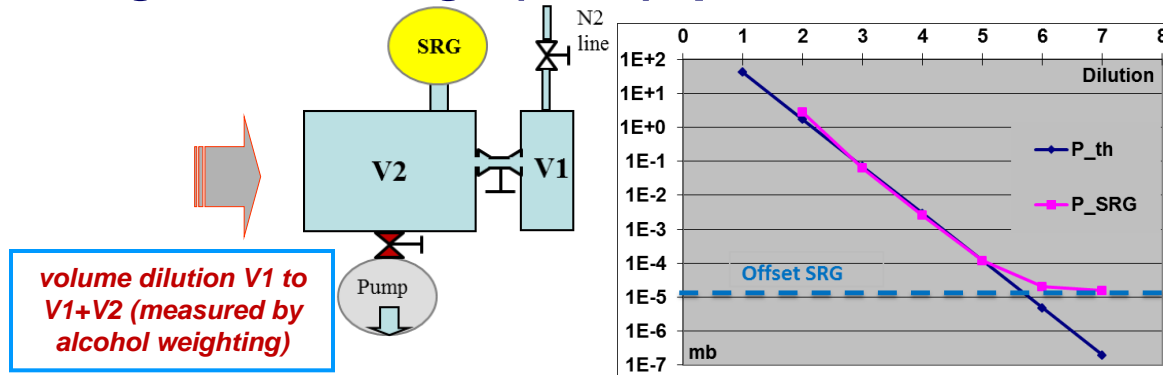
Gases partial pressure inside MEMS cavity? RGA bench needs "calibration" and qualification

RGA bench "calibration"

- 1) "Calibration" of mass spectrometer

- 2) Bench Qualification: Sensitivity, Linearity and Resolution

1) Spinning Rotor Gauge (SRG) qualification



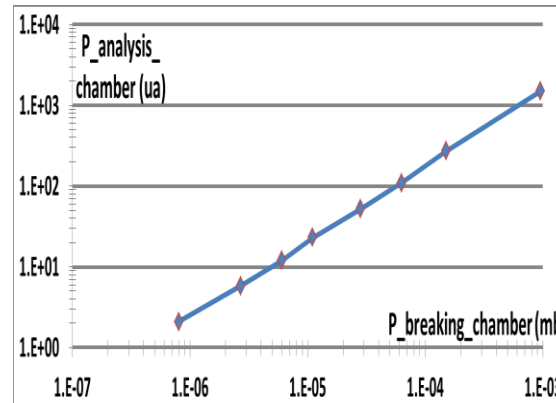
SRG qualified with N2

+

P_ratio_N2

2) $P_{ratio} = P_{breaking_chamber} / P_{analysis_chamber}$?

Pressure ratio between breaking & analysis chamber adjusted & checked on a large pressure range



Spectro "calibrated" on N2 on Faraday cup and 3 Secondary Electrons Multipliers (SEM) ranges

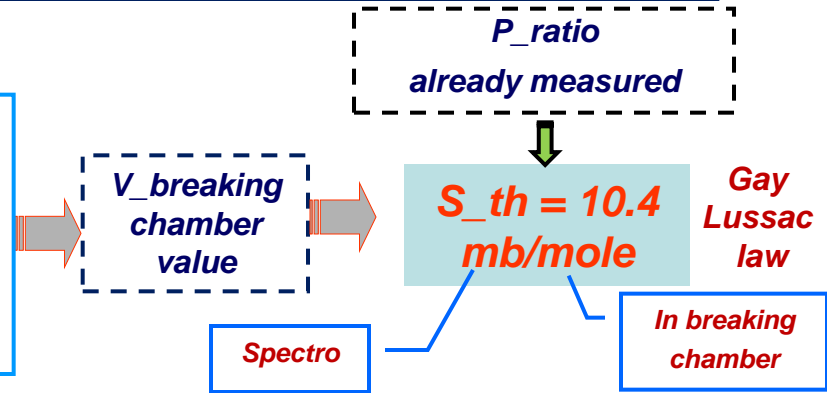
RGA bench qualification

- 1) "Calibration" of mass spectrometer

- 2) Bench Qualification: Sensitivity, Linearity and Resolution

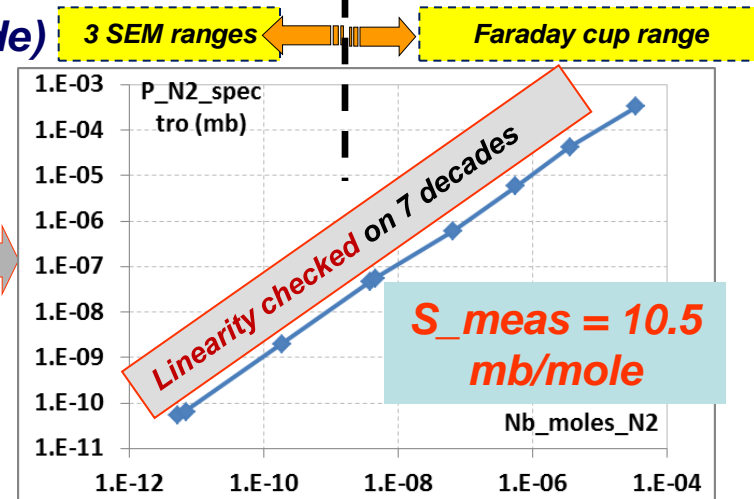
1) Theoretical Sensitivity

Using volumes V_1 , V_2 already accurately measured, volumic dilution & qualified SRG gauge allows $V_{\text{breaking_chamber}}$ measurement



2) Checking Sensitivity & Linearity (RGA mode)

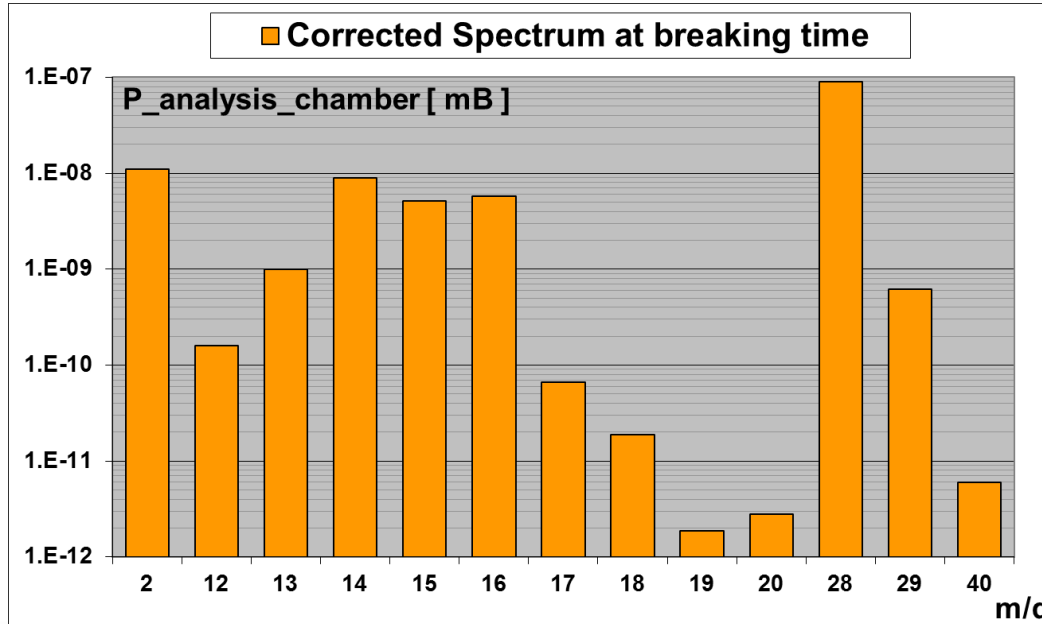
Using qualified SRG gauge, small volume & successive volumic dilutions we checked the RGA bench linearity for N_2 at very low number of moles (10^{-12} range)



3) Resolution = $Nb_moles \leftrightarrow to\ noise = S / S_measured = 4 \cdot 10^{-13}$ moles for N_2 , $4 \cdot 10^{-14}$ for Ar

RGA bench operation & data processing 1/2

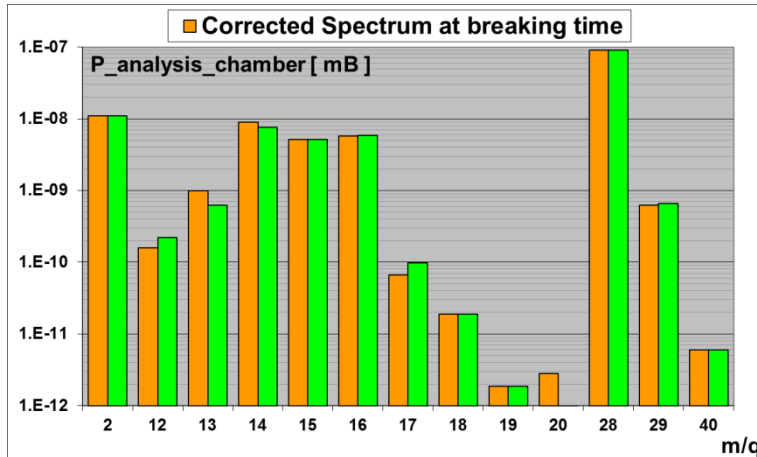
- a) *Spectrum at breaking time– background spectrum (BG) or
Spectrum at breaking time– spectrum at 2nd breaking*
- b) *Correction from diffusion times through diaphragm ($M^{1/2}$).*
- c) *Noise calculation S on each amu using 50 BG spectra*
- d) *Selection of peaks with Signal/Noise > 3.*
- e) *Corrected spectrum at breaking time*



Need of a solver to fit a solution according to molecule's cracking pattern: Each peak can be issued from # gases (ex: peak 28 from N₂, CO, CO₂, C₂H₆ and derivative molecules, ...)

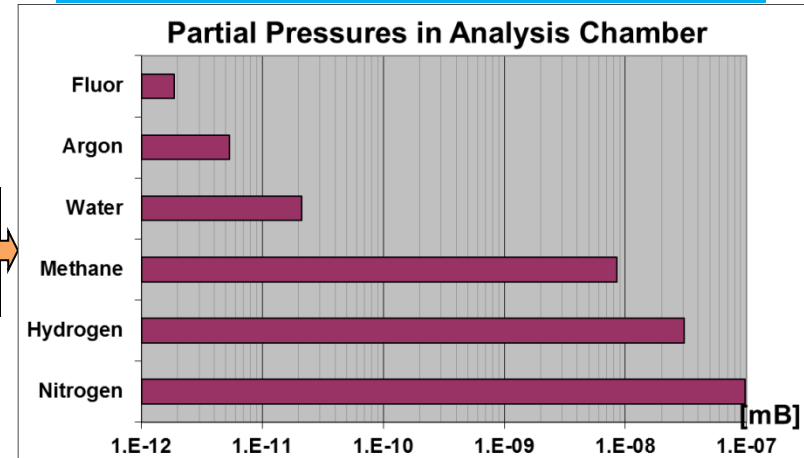
RGA bench data processing 2/2

LETI solver uses gases cracking pattern tables to determine gases molecular's ratio.

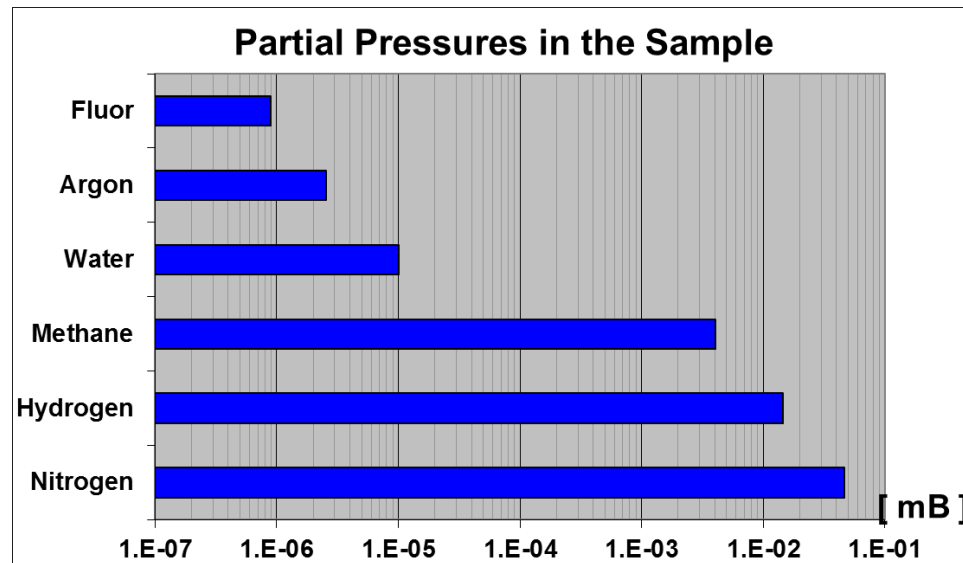


ionization factors correction

Corrections using ionization cross sections for identified gases.



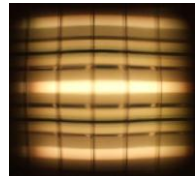
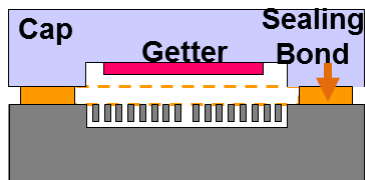
Using Sensitivity for identified gases & the volume of the sample



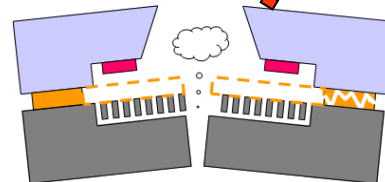
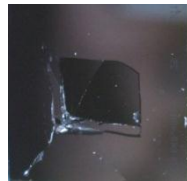
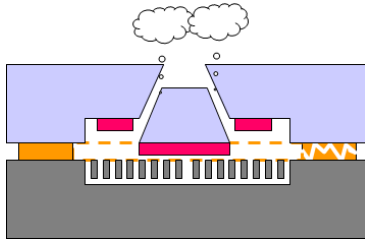
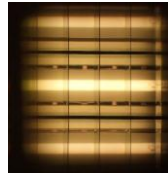
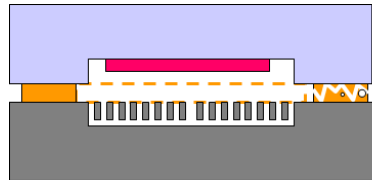
RGA analysis: Some results

Specific UHV tools & micrometrics mechanical

feedthrough to "open" MEMS



Optical reflexion on cap



<i>Thinned cap device</i>					
10^{-12} moles	CH_4	N_2	Ar	C_2H_6	<i>Sum</i>
<i>cavity</i>	<i>6.9</i>	<i>5.5</i>	<i>0.4</i>	<i>0.2</i>	<i>13</i>
<i>cap</i>	<i>0.1</i>	<i>0</i>	<i>0.1</i>	<i>0</i>	<i>0.2</i>
<i>Substrate</i>	<i>0</i>	<i>0.3</i>	<i>1.4</i>	<i>0</i>	<i>1.7</i>

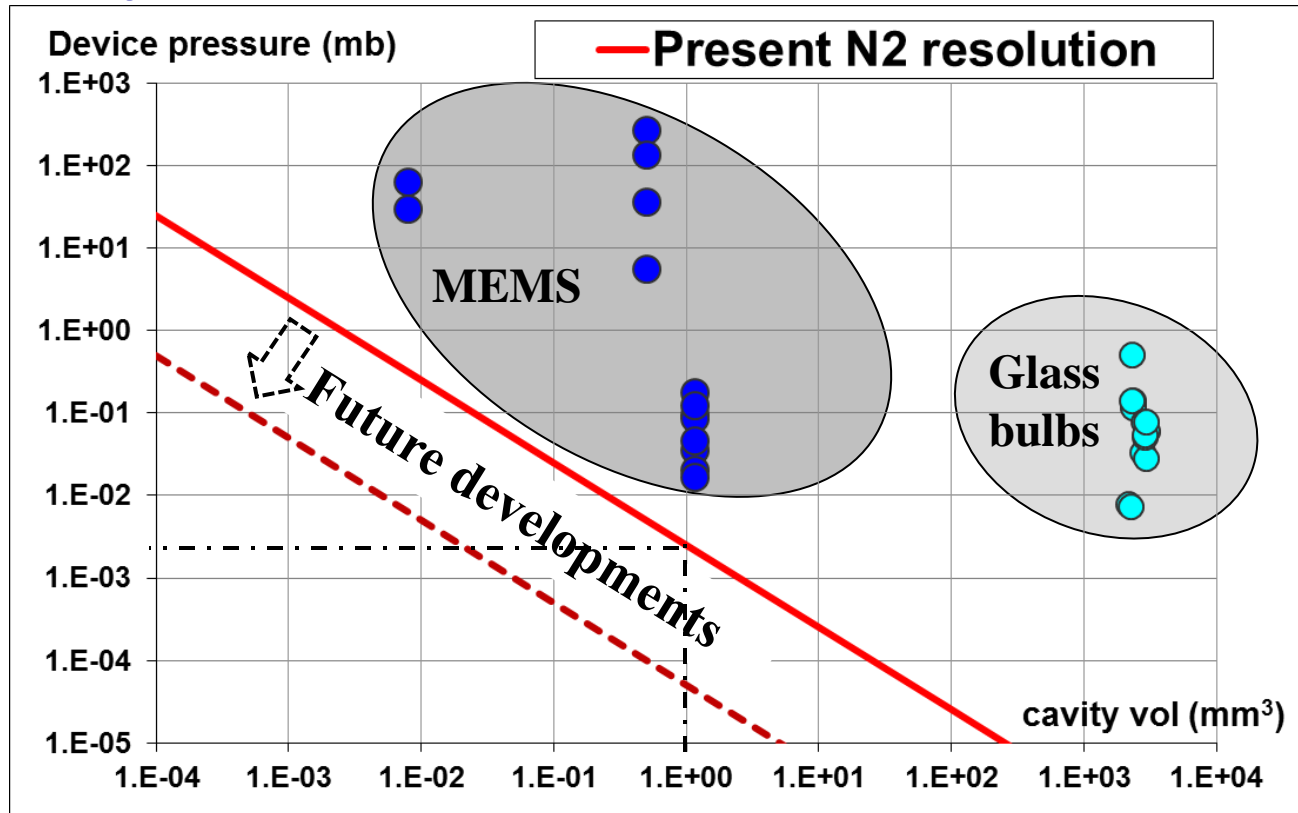
Summary

RGA bench & tools available at LETI

(1 mm³, 10⁻² to 10⁻³ mb resolution)

**material compatibility
with process**

**analyse partial pressures
in sealed MemS**



Conclusions

- *LETI developed a "calibrated" & qualified RGA test bench to assess MEMS reliability in the low pressures & volume ranges (mm^3 , 10^{-3} mb ranges)*
- *RGA tools are of great importance to study and check materials compatibility with MEMS processes and control atmosphere inside packaged devices....*
- *Future developments will focus on a new RGA test bench with enhanced resolution*

leti

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